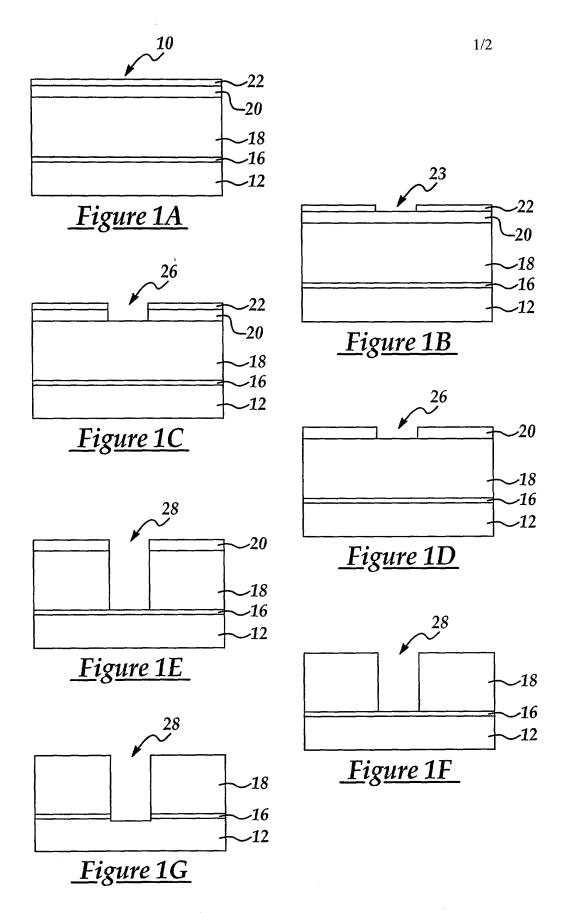
Inventor(s): Tsai, et al Serial No.: To Be Assigned Filed: Herewith

For: A Bi-Layer Photoresist Dry Development ... Ion Etch Method

Attorney Docket No.: 67,200-613



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